



# Bayesian Analysis for Photolithographers

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# Overview

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## ■ Bayesian Analysis

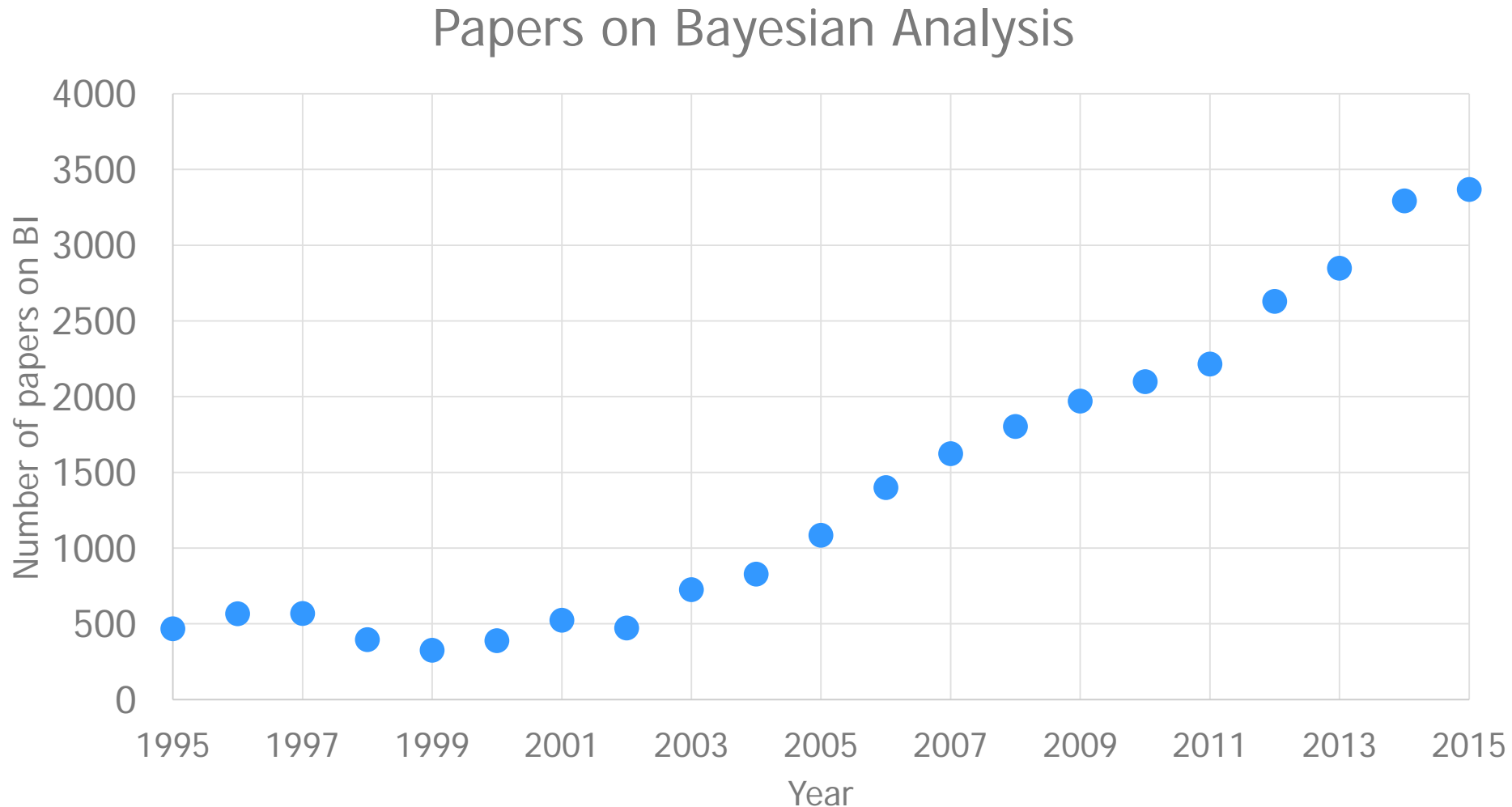
- Probabilistic view of the world
- *A priori* knowledge
- Linear model example

## ■ Uncertainties in OPC model building

- SEM CD measurements
- Physical model parameters

## ■ Prototype, cost functions & insights into the data

# Bayesian Analysis on the Rise



$$p(\{y_i\}|\theta) = \theta^z(1 - \theta)^{N-z}$$

# Bayesian Analysis on a **Bernoulli Trial** Coin

- Determine the probability of heads for a coin

$$p(\{y_i\}|\theta) = \theta^z(1 - \theta)^{N-z}$$

# Bayesian Analysis on a **Bernoulli Trial** Coin

- Determine the probability of heads for a coin
- “Why? It’s probably fair.” ( $\theta = 0.5$ )

## Litho parallel

Determine the value of a mask parameter – absorber sidewall angle

$$p(\{y_i\}|\theta) = \theta^z(1 - \theta)^{N-z}$$

# Bayesian Analysis on a **Bernoulli Trial** Coin

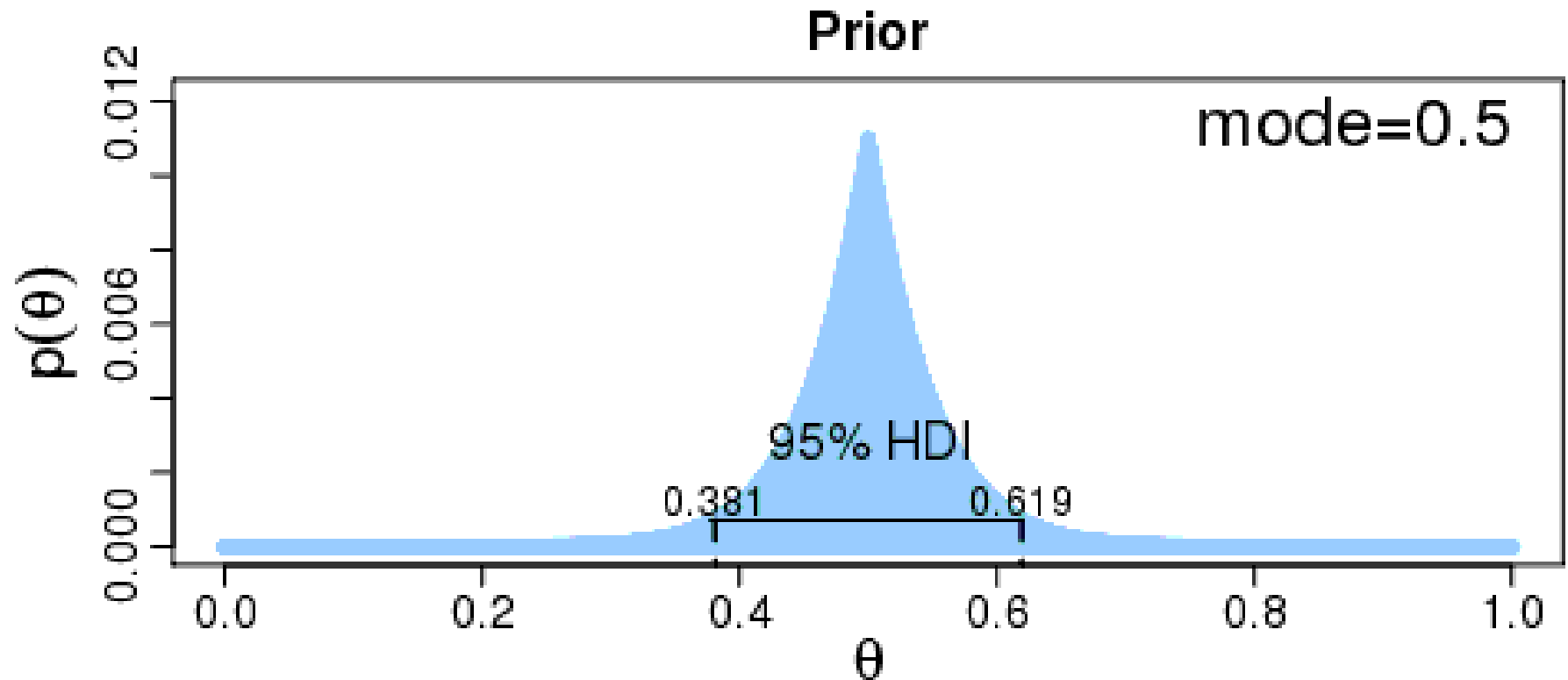
- Determine the probability of heads for a coin
- “Why? It’s probably fair.” ( $\theta = 0.5$ )
- You had *a priori* expectations about the experiment



<https://izbicki.me/blog/how-to-create-an-unfair-coin-and-prove-it-with-math.html>

$$p(\{y_i\}|\theta) = \theta^z(1 - \theta)^{N-z}$$

# Bayesian Analysis on a Bernoulli Trial Coin

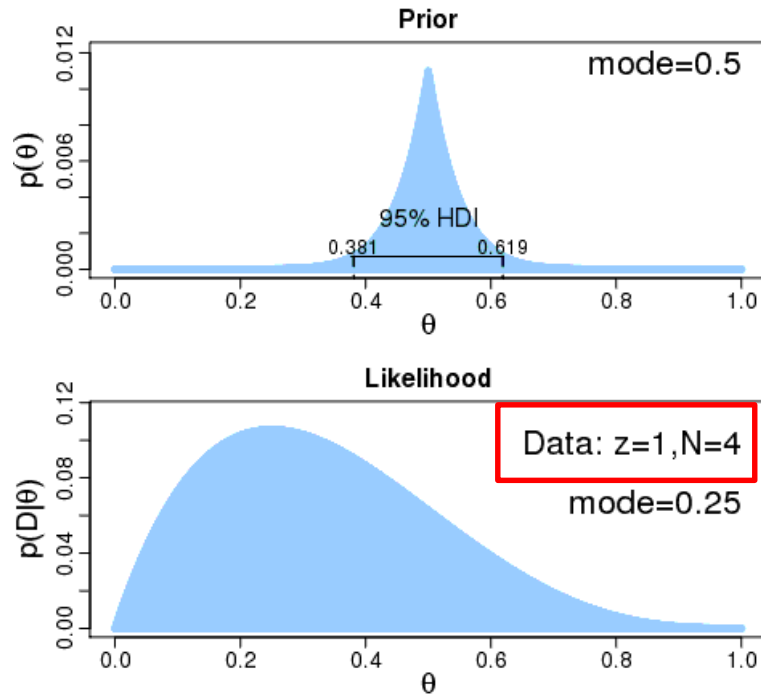


Some metrology data or the  
mask shop specifies:  
SWA = 86°

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$$p(\{y_i\}|\theta) = \theta^z(1 - \theta)^{N-z}$$

# Bayesian Analysis on a Bernoulli Trial Coin

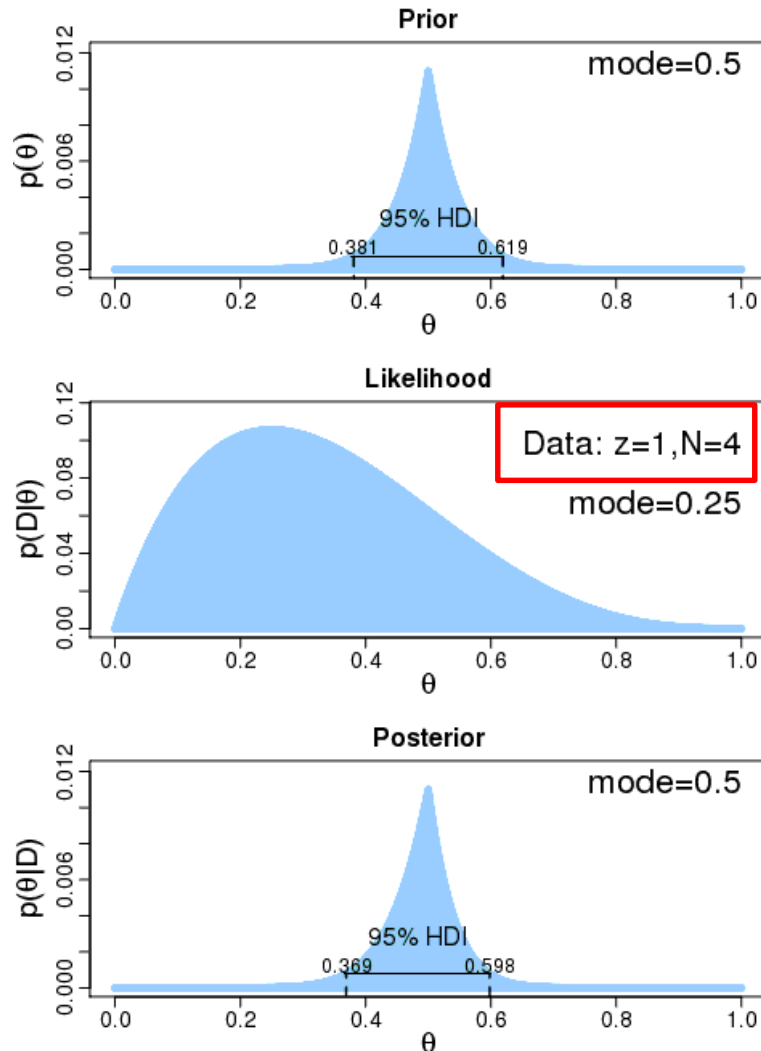


Running a few simulations suggests perhaps 86° isn't correct...



$$p(\{y_i\}|\theta) = \theta^z(1 - \theta)^{N-z}$$

# Bayesian Analysis on a Bernoulli Trial Coin

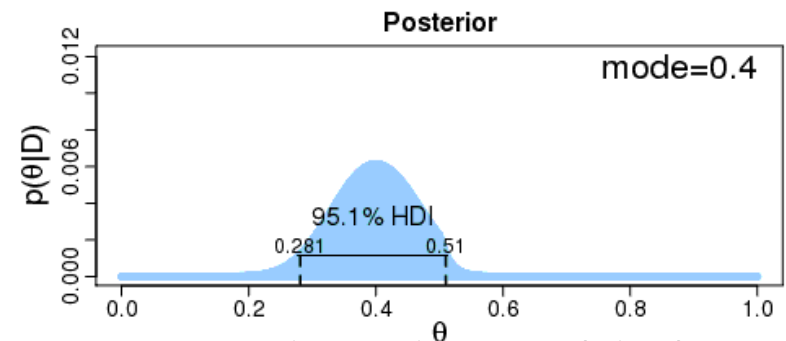
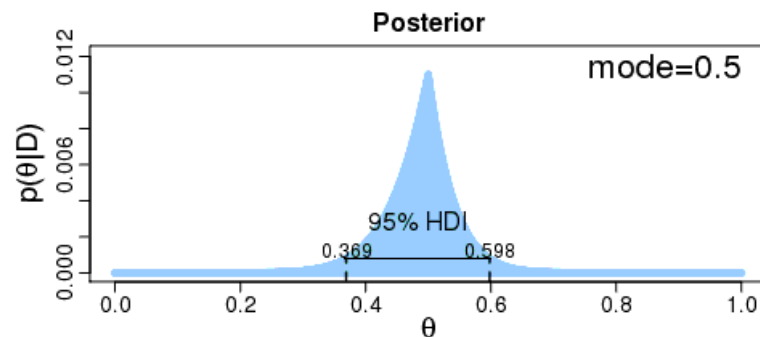
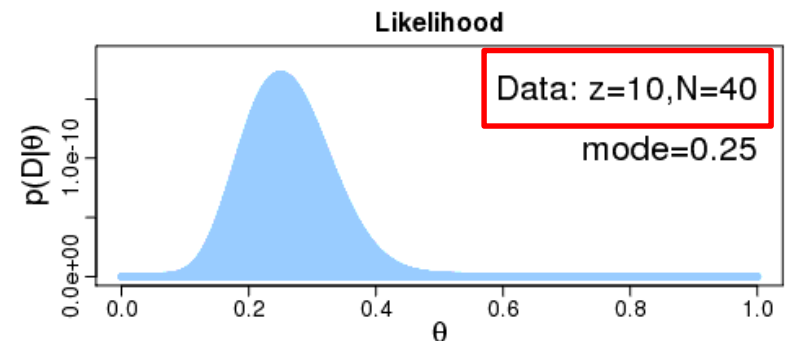
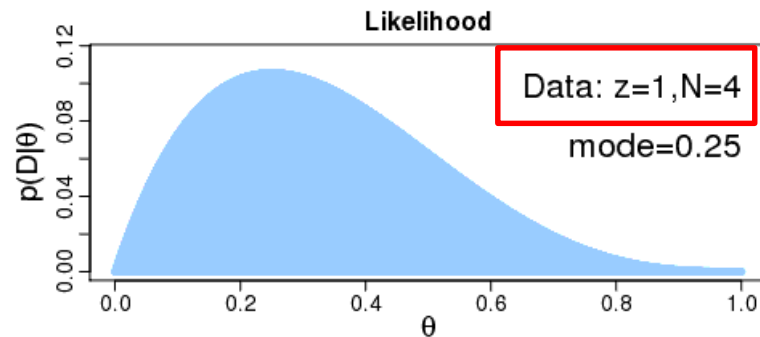
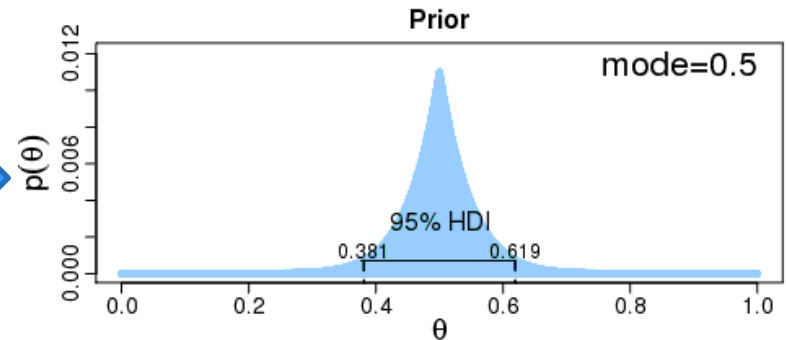
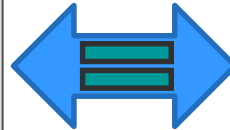
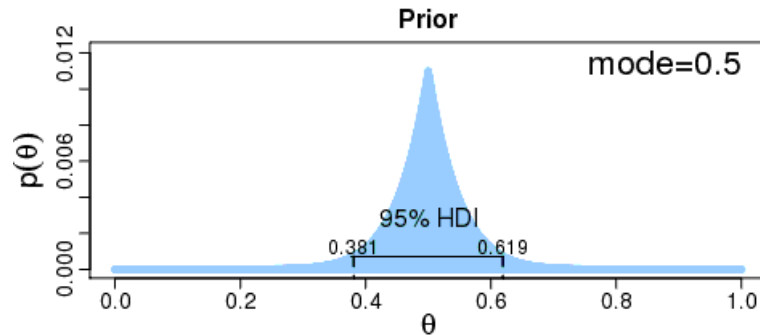


Still, 86° is more credible than the other values based on the information prior to the few simulations

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$$p(\{y_i\}|\theta) = \theta^z(1 - \theta)^{N-z}$$

# Bayesian Analysis on a Bernoulli Trial Coin



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# Bayesian Analysis

Bayes' rule:  $p(\theta|D) = \frac{p(D|\theta) \cdot p(\theta)}{p(D)}$

- The **prior** is the credibility of the parameters  $\theta$  without the data  $D$
- The **likelihood** is the probability that the data could be generated by the model with parameter value  $\theta$
- The **evidence** is the overall probability of the data according to the model, determined by averaging across all possible parameter values
- The **posterior** is the credibility of the parameters  $\theta$  given the data  $D$

# Analysis on a Simple Linear Model

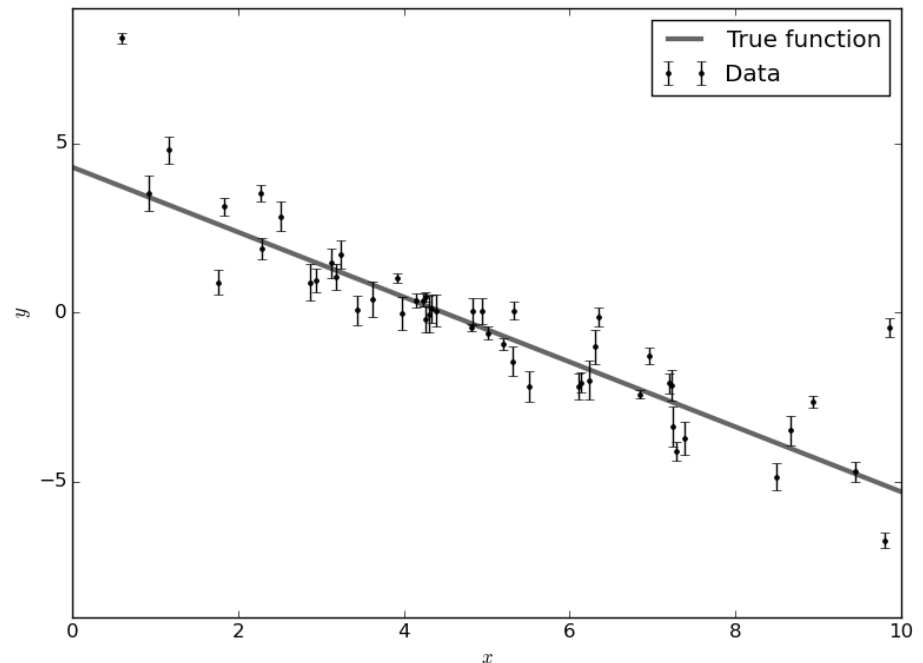
- x by y linear model
  - Underestimated uncertainties in the error of y
- Generate 50 data points
- Fit a line to the data
- Seeking to find the values for the coefficients in model:
  - $y = mx + b \pm \epsilon(f)$
- We have many choices for obtaining such parameters...

$$m_{true} = -0.9594$$

$$b_{true} = 4.294$$

$$f_{true} = 0.534$$

$$y = m_{true}x + b_{true} + |f_{true}y| \cdot U(0,1)$$



<http://dan.iel.fm/emcee/current/user/line/>

CD measurements have uncertainty associated with their values (measurement variability, site accuracy)

# Applying Bayes Rule

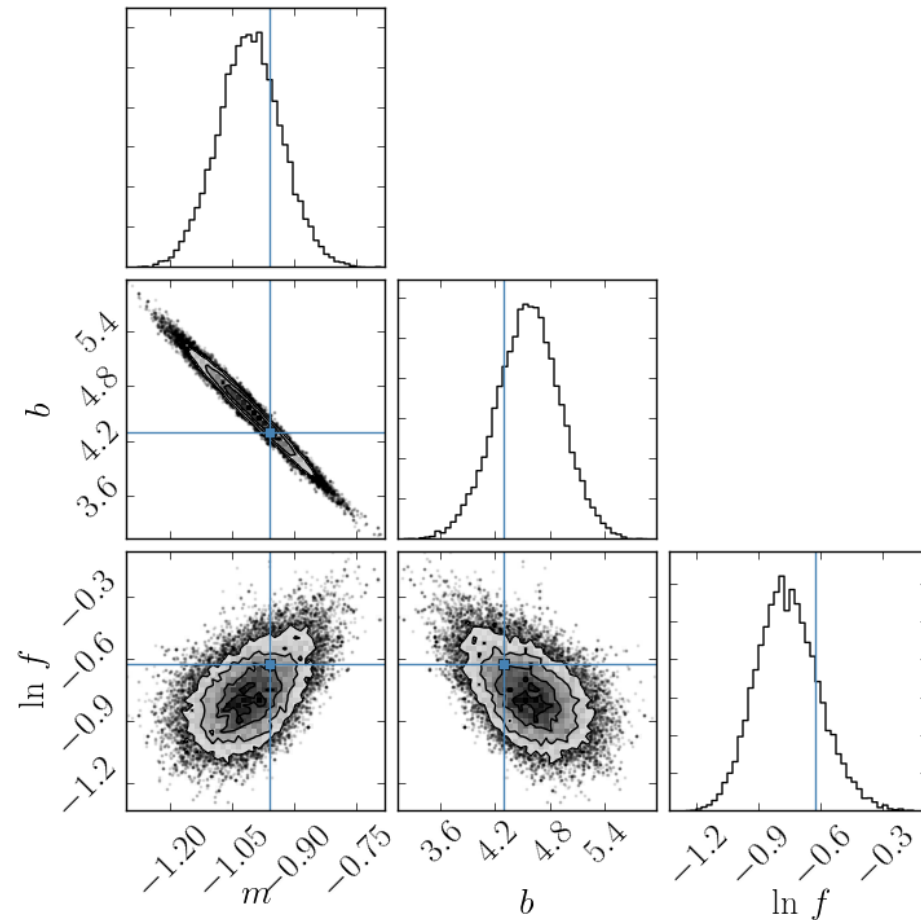
- In order incorporate our prior knowledge and generate posteriors for the parameters in the model, we must evaluate:

$$p(m, b, \sigma, f|D) = \frac{p(D|m, b, \sigma, f) p(m, b, \sigma, f)}{\iint \iint p(D|m, b, \sigma, f) p(m, b, \sigma, f) dm db d\sigma df}$$

- Intractable integral for any real world problem
  - Conjugate priors exist for few modeling problems
  - Empirical solutions only for complex models
- We must computationally explore the parameter space
  - Increased computational power and algorithms in the past decade have enabled Bayesian Analysis

# Markov Chain Monte Carlo

- MCMC methods are a class of algorithms designed to explore parameter spaces
- Move proposals
  - Some simple, some complex
  - Accepted or rejected based on certain criterion
- Empirical posterior distributions are generated which indicate highest credibility parameters



<http://dan.iel.fm/emcee/current/user/line/>

# Model Parameters with Uncertainty

- Using the AIES sampler, 50,000 models are explored
- Posteriors (previous slide) are generated
- From the posteriors:
  - 95% highest density intervals
  - *Maximum a posteriori probability* (MAP)
- Accuracy of the MLE result + uncertainty in parameters
  - Used uninformative priors

$$m_{true} = -0.9594$$

$$b_{true} = 4.294$$

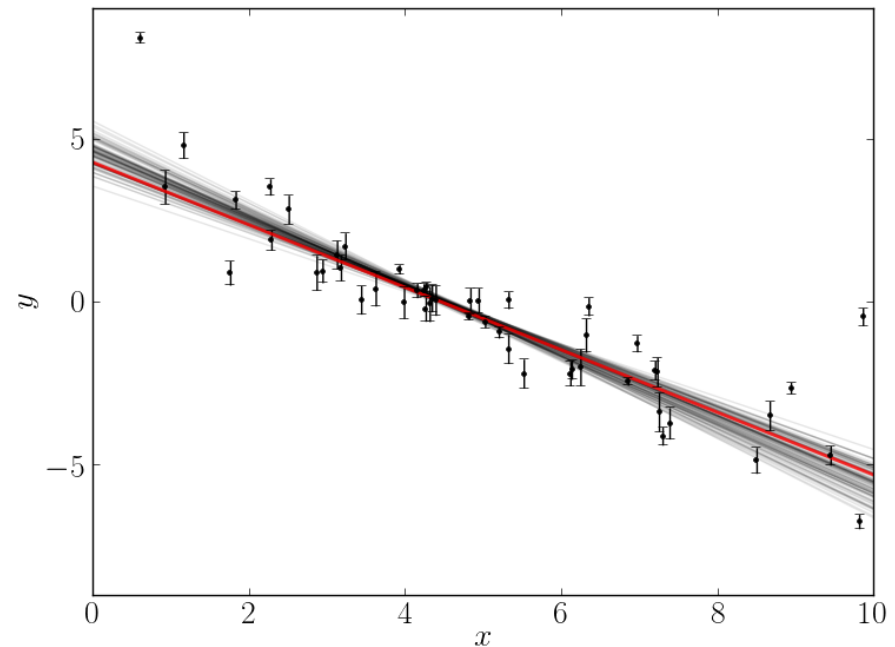
$$f_{true} = 0.534$$

$$m_{bi} = -1.009^{+0.077}_{-0.075}$$

$$b_{bi} = 4.556^{+0.346}_{-0.353}$$

$$f_{bi} = 0.463^{+0.079}_{-0.063}$$

$$y = m_{true}x + b_{true} + |f_{true}y| \cdot U(0,1)$$

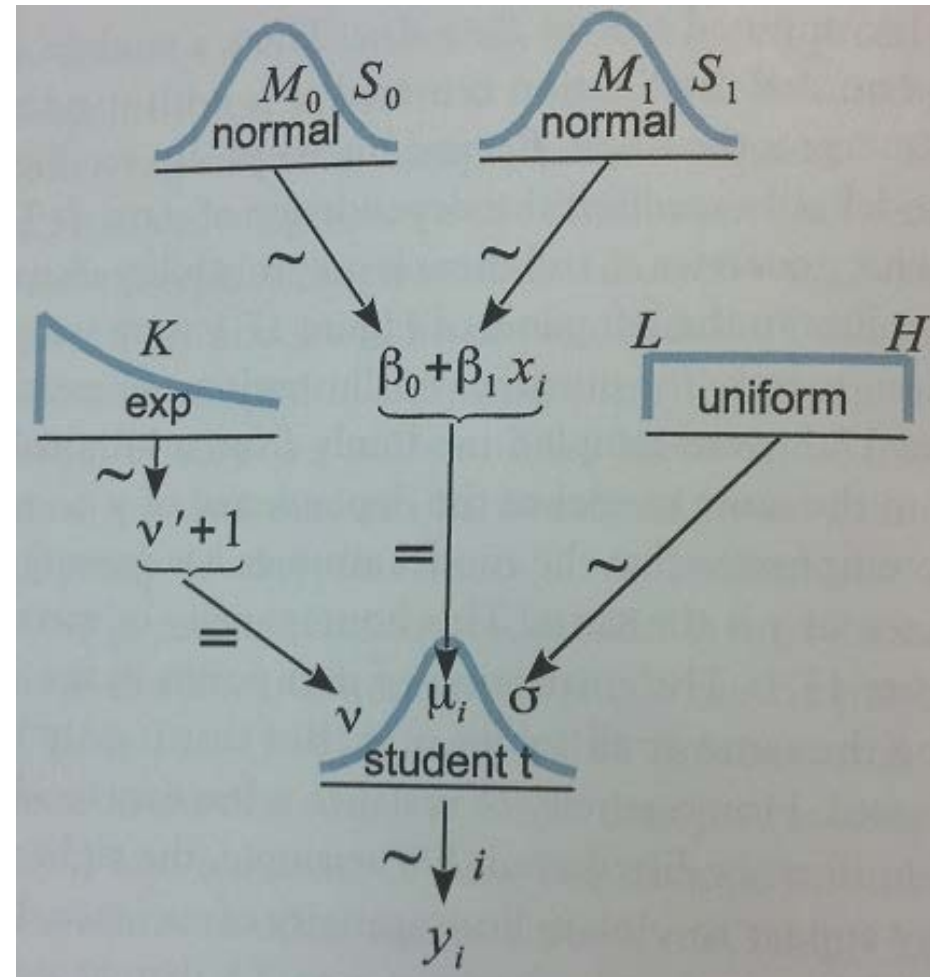


<http://dan.iel.fm/emcee/current/user/line/>

# Bayesian Model Hierarchy

- Add to the prior knowledge by building a set of dependencies
- Model to predict baseball hitter's batting average
  - Past performance indicates odds
  - Expect first baseman to have higher BA
  - Position average informs player average

2D structures expected to have more uncertainty than pitch structures



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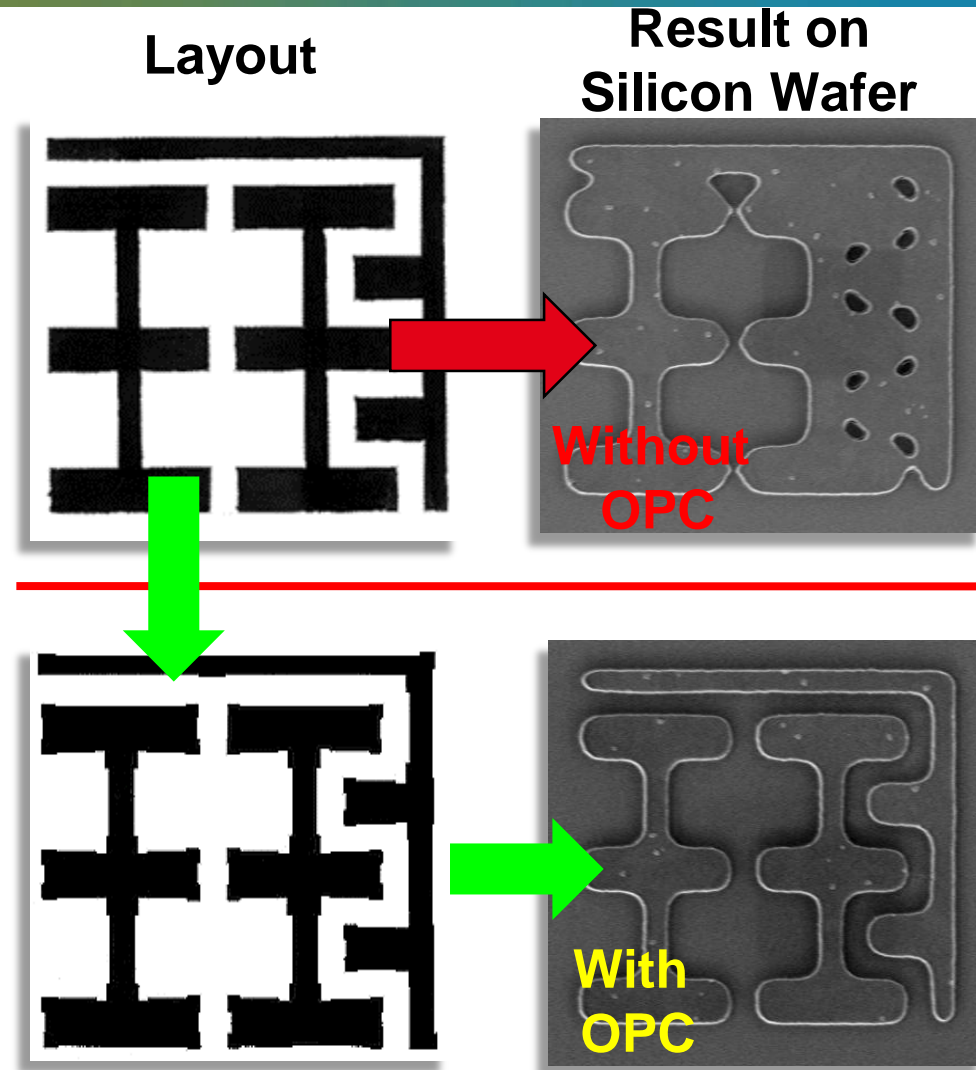


# *Optical Proximity Correction*

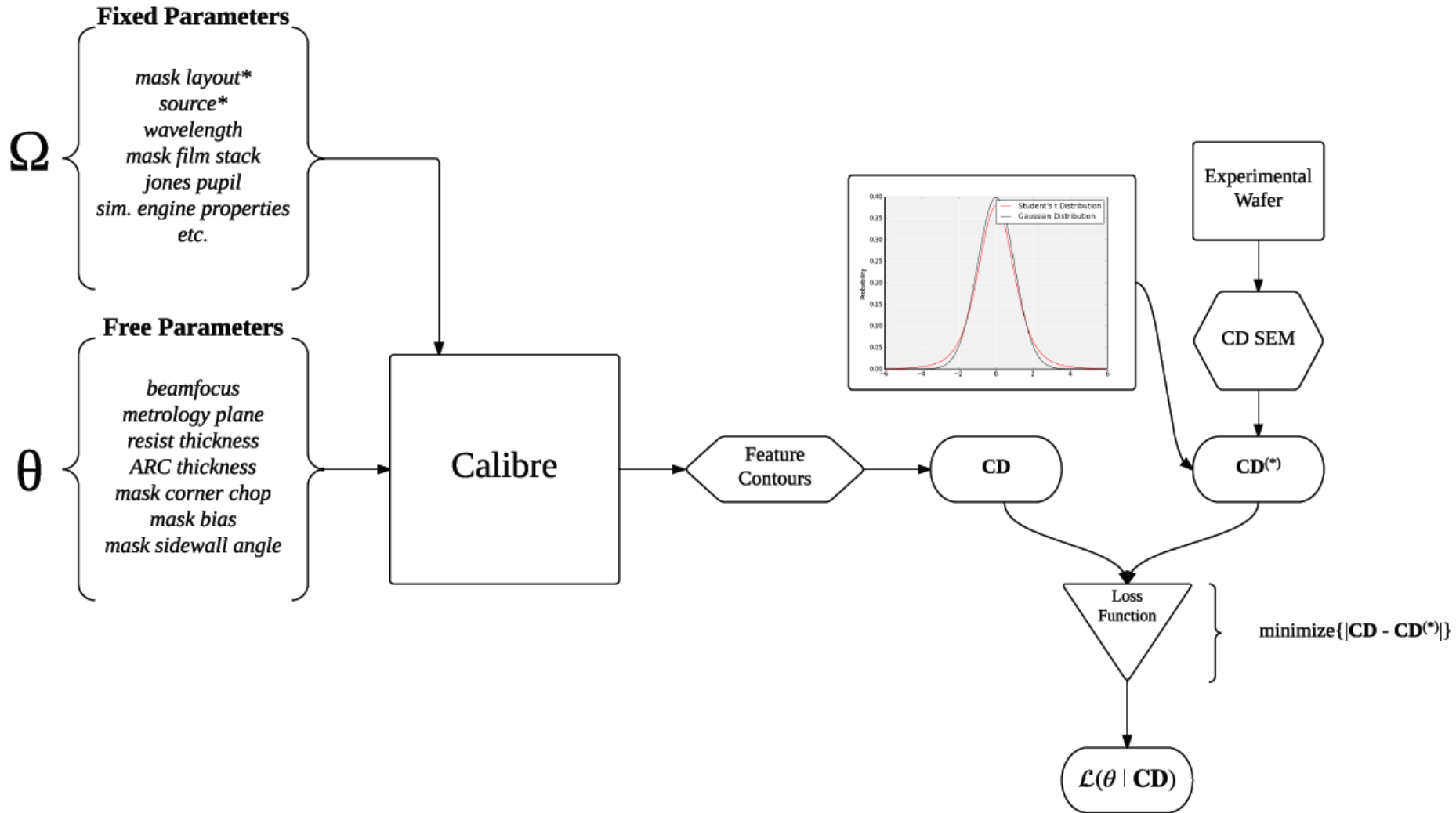
*Pushing the limits of lithographic printability*

# Optical Proximity Correction

- Because optical lithography is performed near the physical limits of its manufacturing systems, advanced techniques, such as optical proximity correction (OPC) are needed to achieve the design intent
- On the right there are two examples of going from the layout (mask) to exposure in photoresist
- The edges of the layout are modified, algorithmically, so that the actual printed design is closer to the original layout than it would otherwise be



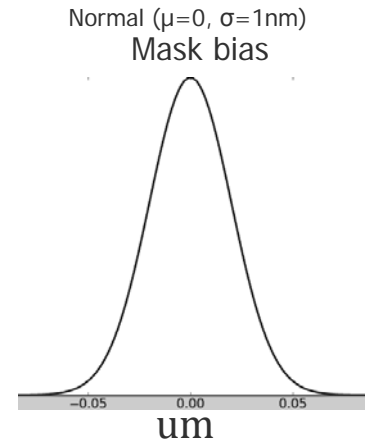
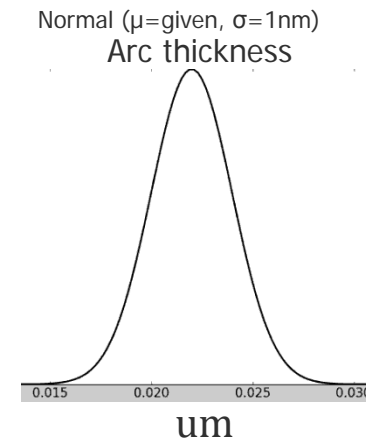
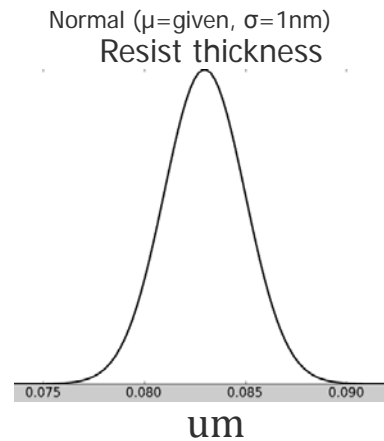
# Photolithographic Model Parameters & Uncertainty



# Assumptions and Distributions

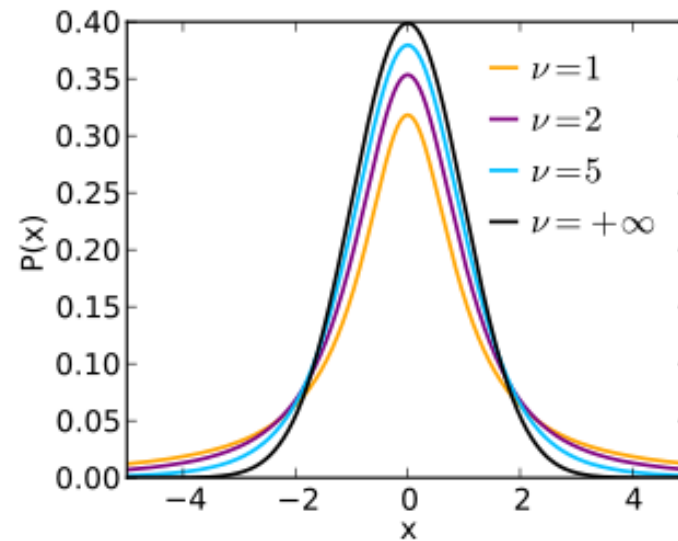
*Physical  
parameters*

*Normally  
distributed*

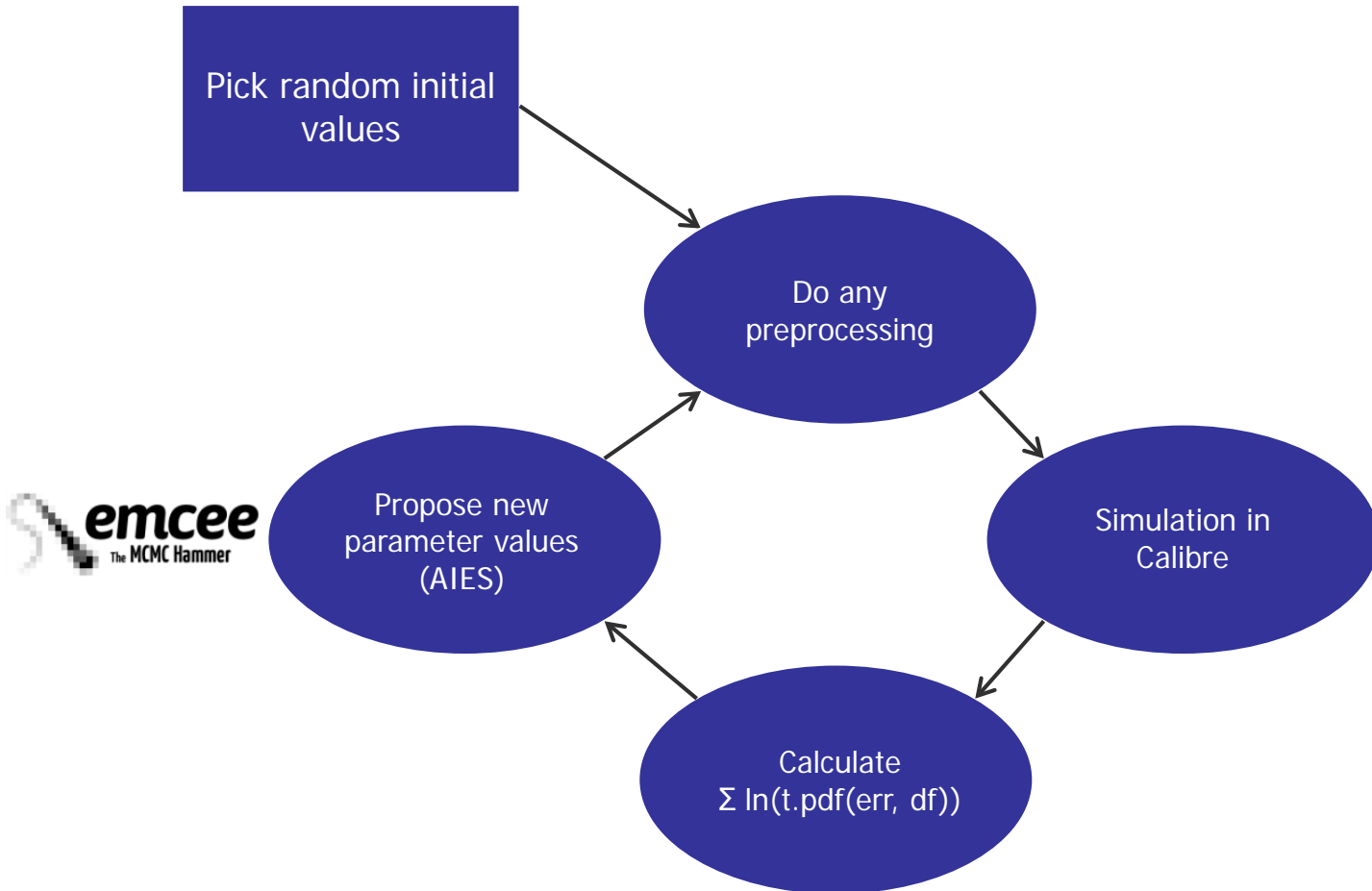


*CD Measurements*

*Student's t-distributed*

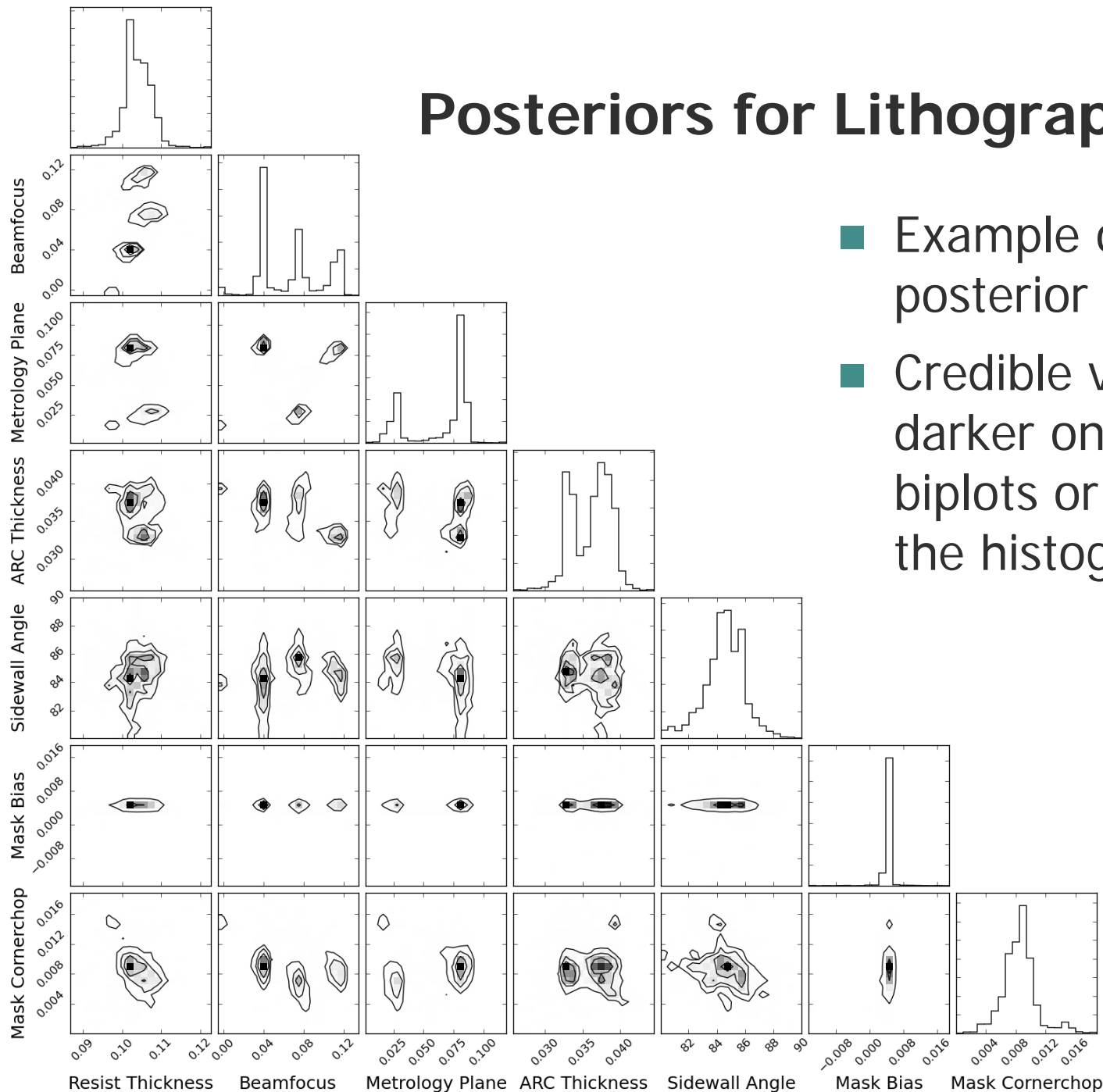


# Workflow (Prototype)



<http://dan.iel.fm/emcee/current/>

# Posteriors for Lithographic Models



- Example of parameter posterior distributions
- Credible values are darker on the 2D biplots or the peaks of the histograms

# Posterior Predictive Check

- Train model with a subset of CD measurements
  - 100 measurements
- Evaluate model on larger set of CD measurements
  - 1000 measurements
- This is a 'sanity check' on the parameter values
- Evaluate against *traditional* (non-Bayesian) methods
  - Trained on the *full* dataset
- Best traditional RMSe
  - 4.11
- Best Bayesian RMSe
  - 3.97

# Conclusions

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- Markov Chain Monte Carlo methods are effective at optimizing many parameters in parallel
  - This is particularly important for the hefty full-chip OPC models used in manufacturing, which can take a significant amount of computational time to build and evaluate
- Uncertainties in modeling can be captured
  - Wafer CD data and model parameter information is imperfect
  - Acknowledging this under the Bayesian framework is beneficial
- Evaluation over traditional methods
  - Bayesian method with expanded parameter set finds more accurate models than traditional methods
  - Key feature: models are trained on only a subset of the data, giving them a very small over-fit risk





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